| L Number | Hits | Search Text | DB | Time stamp |
|---|---|---|---|---|
| - | 607 | "Si.sub.x N.sub.y" | USPAT;<br>US-PGPUB | 2003/05/13 20:05 |
| - | 58366 | CVD | USPAT;<br>US-PGPUB | 2003/05/13 20:05 |
| - | 60364 | chemical$2 adj vapor adj deposit$3 | USPAT;<br>US-PGPUB | 2003/05/13 20:06 |
| - | 501374 | oxide | USPAT;<br>US-PGPUB | 2003/05/13 20:06 |
| - | 110324 | "SiO.sub.2" | USPAT;<br>US-PGPUB | 2003/05/13 20:06 |
| - | 15864 | (CVD or (chemical$2 adj vapor adj deposit$3)) near4 (oxide or "SiO.sub.2") | USPAT;<br>US-PGPUB | 2003/05/13 20:07 |
| - | 10485 | BPSG | USPAT;<br>US-PGPUB | 2003/05/13 20:07 |
| - | 12885 | TEOS | USPAT;<br>US-PGPUB | 2003/05/13 20:07 |
| - | 493 | (trench near isolation) and ((thermal$2 near3 oxid$5) same ((silicon adj nitride) or "si.sub.3 N.sub.4" or "Si.sub.x N.sub.y") same (((CVD or (chemical$2 adj vapor adj deposit$3)) near4 (oxide or "SiO.sub.2")) or BPSG or TEOS)) | USPAT;<br>US-PGPUB | 2003/05/13 21:10 |
| - | 619 | atomic adj layer adj deposition | USPAT;<br>US-PGPUB | 2003/05/13 21:14 |
| - | 267 | (atomic adj layer adj deposition) and (((silicon adj nitride) or "si.sub.3 N.sub.4" or "Si.sub.x N.sub.y") and (oxide or "SiO.sub.2")) | USPAT;<br>US-PGPUB | 2003/05/13 21:48 |
| - | 371 | (chemical$2 adj vapor adj deposit$3) same (atomic adj layer adj deposition) | USPAT;<br>US-PGPUB | 2003/05/13 21:49 |

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